

L Number	Hits	Search Text	DB	Time stamp
1	339	((348/300) or (348/301) or (348/308)).CCLS.	USPAT	2003/01/15 13:28
-	1504	(250/208.1).CCLS.	USPAT	2003/01/15 13:28
-	67	hatano-keisuke\$.in.	USPAT	2002/12/18 09:59
-		nakashiba-yasutaka\$.in.		
-	229	((250/208.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1	USPAT	2003/01/13 08:25
-	38	((250/208.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$3	USPAT	2002/12/18 10:56
-	38	((250/208.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$4	USPAT	2003/01/13 13:12
-	9	((250/214.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$4	USPAT	2003/01/13 13:31
-	38	((250/208.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$4	USPAT	2003/01/13 13:34
-	7	((250/214.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$4 not ((250/208.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$4 )	USPAT	2003/01/13 13:13
-	4	((250/214r).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$4	USPAT	2003/01/13 13:32
-	2	((250/214r).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$4 not ((250/208.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$4 )	USPAT	2003/01/13 13:32
-	17	(insulat\$3 adj (film\$1 or layer\$1)) same isolat\$4 near2 electrode\$1 and 250/\$.ccls.	USPAT	2003/01/13 13:45
-	630	(insulat\$3 adj (film\$1 or layer\$1)) same isolat\$4 near2 electrode\$1 and 257/\$.ccls.	USPAT	2003/01/15 09:30
-	624	((insulat\$3 adj (film\$1 or layer\$1)) same isolat\$4 near2 electrode\$1 and 257/\$.ccls.) not ((insulat\$3 adj (film\$1 or layer\$1)) same isolat\$4 near2 electrode\$1 and 250/\$.ccls.)	USPAT	2003/01/13 13:46
-	624	((insulat\$3 adj (film\$1 or layer\$1)) same isolat\$4 near2 electrode\$1 and 257/\$.ccls.) not ((insulat\$3 adj (film\$1 or layer\$1)) same isolat\$4 near2 electrode\$1 and 250/\$.ccls.) not ((250/208.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1 same isolat\$4 )	USPAT	2003/01/14 14:20
-	5	("4751559"   "4812869"   "5010245"   "5029998"   "5483318").PN.	USPAT	2003/01/14 10:30
-	1984	(electrode\$1) with polysilicon with silicide	USPAT	2003/01/14 14:33
-	3	(isolat\$3 adj electrode\$1) with constant with voltage\$1	USPAT	2003/01/14 14:42
-	0	(isolat\$3 adj electrode\$1) with constant with voltage\$1	EPO; JPO; DERWENT; IBM_TDB	2003/01/14 14:42
-	28	(isolat\$3 adj electrode\$1) with voltage\$1	EPO; JPO; DERWENT; IBM_TDB	2003/01/14 14:49
-	13	sasaki-michio\$.in.	USPAT	2003/01/14 14:49
-	0	insulat\$3 same flow\$3 same heat\$3 same electrode\$1 same flatten\$3 same etch\$3 same bury\$3	USPAT	2003/01/15 07:59

-	1	insulat\$3 same heat\$3 same electrode\$1 same flatten\$3 same etch\$3 same bury\$3	USPAT	2003/01/15 08:00
-	9	insulat\$3 same heat\$3 same flatten\$3 same etch\$3 same bury\$3	USPAT	2003/01/15 08:07
-	1	insulat\$3 same heat\$3 same flatten\$3 same etch\$3 same (bury\$3 or buried) same electrode\$1	USPAT	2003/01/15 08:07
-	8	insulat\$3 same heat\$3 same flatten\$3 same etch\$3 same (bury\$3 or buried) same electrode\$1	EPO; JPO; DERWENT; IBM_TDB	2003/01/15 08:10
-	3	insulat\$3 same heat\$3 same flatten\$3 same (bury\$3 or buried) same electrode\$1	USPAT	2003/01/15 08:12
-	15	insulat\$3 same heat\$3 same flatten\$3 same (bury\$3 or buried) same electrode\$1	EPO; JPO; DERWENT; IBM_TDB	2003/01/15 08:24
-	133	insulat\$3 with (bury\$3 or buried) same electrode\$1 same heat\$3	USPAT	2003/01/15 08:24
-	26	insulat\$3 with (bury\$3 or buried) same electrode\$1 same heat\$3 and flatten\$3	USPAT	2003/01/15 08:25
-	15	insulat\$3 with (bury\$3 or buried) same electrode\$1 same heat\$3 and flatten\$3 same heat\$3	USPAT	2003/01/15 08:29
-	4	insulat\$3 with (bury\$3 or buried) with (flow\$3 or heat\$3) same electrode\$1 and flatten\$3 with heat\$3	USPAT	2003/01/15 08:31
-	130	insulat\$3 with (flow\$3 or heat\$3) same electrode\$1 and flatten\$3 with heat\$3	USPAT	2003/01/15 08:31
-	5	insulat\$3 with (flow\$3 with heat\$3) same electrode\$1 and flatten\$3 with heat\$3	USPAT	2003/01/15 08:46
-	35	(insulat\$3 or bpsg) with (reflow\$3) same electrode\$1 and (flatten\$3 or flat) with heat\$3	USPAT	2003/01/15 08:48
-	23	(insulat\$3 adj (film\$1 or layer\$1)) same isolat\$4 near2 electrode\$1 and 348/\$.ccls.	USPAT	2003/01/15 09:31